

L Number	Hits	Search Text	DB	Time stamp
1	52259	(mask or reticle or original) same (pinhole or hole)	USPAT; EPO; JPO; DERWENT	2002/09/09 09:25
2	23007	(mask or reticle or original) near8 (pinhole or hole)	USPAT; EPO; JPO; DERWENT	2002/09/09 09:26
3	11092	((mask or reticle or original) near8 (pinhole or hole)) and (substrate or wafer or target)	USPAT; EPO; JPO; DERWENT	2002/09/09 09:28
4	1565	((((mask or reticle or original) near8 (pinhole or hole)) and (substrate or wafer or target)) and (355/\$.ccls. or 356/\$.ccls. or 250/\$.ccls. or 430/\$.ccls.))	USPAT; EPO; JPO; DERWENT	2002/09/09 09:29
5	119	(((((mask or reticle or original) near8 (pinhole or hole)) and (substrate or wafer or target)) and (355/\$.ccls. or 356/\$.ccls. or 250/\$.ccls. or 430/\$.ccls.)) and (((sens\$4 or detect\$4 or measu\$4) near5 (intensity or exposure)) same (wafer or substrate))	USPAT; EPO; JPO; DERWENT	2002/09/09 09:59